In the Claims:

Please cancel claims 1, 3 and 8-12 without prejudice or disclaimer.

Please amend claim 6 as follows:

Claim 1 (currently canceled)

Claim 2 (previously canceled)

Claim 3 (currently canceled)

Claims 4-5 (previously canceled)

Claim 6 (currently amended) The photoresist composition of claim 3 A photoresist composition comprising:

a photoresist polymer, a photoacid generator, an additive of following Formulas 3-7 and an organic solvent,

Formula 3

Formula 4

Formula 5

Formula 6

Formula 7

wherein the photoresist polymer is a compound of following Formulas 8 or 9:

Formula 8

Formula 9

wherein, R₁ is and acid labile protecting group;

R₂ is hydrogen;

 R_3 is hydrogen, selected from the group consisting of C_1 - C_{10} alkyl, C_1 - C_{10} alkoxyalkyl, and C_1 - C_{10} alkyl containing at least one hydroxyl group (-OH);

n is an integer from 1 to 5; and

w, x, y and z individually denote the mole ratio of each monomer, preferably with proviso that w + x + y = 50 mol%, and z is 50 mol%.

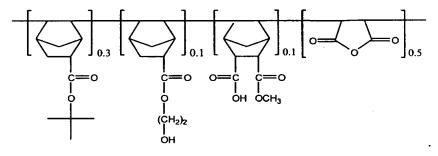
Claim 7 (previously amended) The photoresist composition of claim 6 wherein the photoresist polymer is selected from the group consisting of compounds of following Formulas 10 to 13:

Formula 10

Formula 11

Formula 12

Formula 13



Claims 8-12 (currently canceled)

Claims 13-20 (previously canceled)